



Docket No.: M4065.0237/P237
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Mark Fischer et al.

Application No.: 10/768,081

Confirmation No.: 8284

Filed: February 2, 2004

Art Unit: 2815

For: DOUBLE BLANKET ION IMPLANT
METHOD AND STRUCTURE

Examiner: E.J. Wojciechowicz

RESPONSE TO RESTRICTION REQUIREMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The Restriction Requirement mailed January 25, 2005 (Paper No. 0120),
required restriction between:

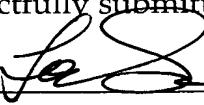
Group I. Claims 56-70, drawn to a semiconductor device; and

Group II. Claims 40-55 and 71-75, drawn to a method of making a semiconductor
device.

In response, Applicant hereby elects Group I, claims 56-70 for continued examination,
without traverse.

Dated: February 7, 2005

Respectfully submitted,

By 

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